



Name of article	Weave 700	Secondary backing ISO 2424	Action back
Method of production ISO 2424	Flat woven	Electrostatic loading ISO 6356	< 2 KV
Width ISO 3018	ca. 400	Surface resistivity ISO 10965 ROT	
Surface structure ISO 2424	Loop	Transparency to heat ISO 8302	0,09 K*m ² /W
Colourways	Mix	Light fastness ISO 105-B02	≥ 5
Pile material ISO 2424	100% PA 6.6	Water fastness EN ISO 105 E01	≥ 4
Primary backing ISO 2424	PA, PES	Friction fastness EN ISO 105-X12	≥ 3-4
Overall weight ISO 8543	ca. 2200 g/m ²	Stitch rate ISO 1763	ca. 188.000/m ²
Overall thickness ISO 1765	ca. 3,50 mm		
Pile service weight	ca. 750 g/m ²		



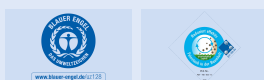
EN 14041 | DOP: 1060-OC-6323-C2
CPR: 0809-CPR-19006323 - C2 | NB: 1658

Health-promoting properties AIR



- Free from PVC and bitumen.
- Free from formaldehyde.
- Reduction of fine dust in the breathing air.
- Free from harmful emissions and odors.
- TVOC limits are immediately met.
- Suitable for allergy sufferers

HEALTH



Health-promoting ACOUSTIC properties



- Improved impact sound insulation +18dB
- Enhanced room acoustics +0.15α_w

Hz	125	250	500	1000	2000	4000
α _s	0,00	0,00	0,05	0,20	0,15	0,10

- Increased employee concentration and motivation through enhanced well-being
- Acoustically effective



Environmental properties

CAFA79F9
PRODID | product pass

- Recycled primary backing
- Easy cleaning with water only



Product Information

The weave quality with a spindle-like design creates an original surface structure. Seam markings on small-patterned flatweaves are typical of the fabric. The reason for the occasional zipper effect in the appearance at the seam edges is not due to the design, but to the fabric construction or patterning.

Installation Instructions

The precise seam cut is carried out professionally using a steel ruler and a laying knife with a trapezoidal blade. The use of pile scissors is recommended for processing cut studs to ensure a flawless appearance.



Made in Europe (production according to EU standard)

Data status 30.06.2025. Subject to changes due to technical advancements.